

AMENDMENTS TO THE CLAIMS:

This listing of claims will replace all prior versions, and listings, of claims in the application:

LISTING OF CLAIMS:

1. (original) An exposure apparatus which exposes an object with an illumination beam irradiated on a mask from a light source, comprising:

an illumination optical system disposed on an optical path along which the illumination beam passes to illuminate the mask with the illumination beam through an optical integrator; and

an optical unit disposed between the light source and the optical integrator in the illumination optical system to form different intensity distributions of the illumination beam on a Fourier transform plane with respect to a pattern surface of the mask, the optical unit including a deflection optical element that generates a deflected beam in a different direction from an optical axis of the illumination optical system to form one of the different intensity distributions having an increased intensity portion apart from the optical axis relative to a portion of the one intensity distribution on the optical axis, an optical element movable along the optical axis and a zoom optical

system to adjust at least one of the different intensity distributions.

Claims 2-54 (cancelled)